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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
10/006,704	12/10/2001	Shane J. Trapp	M4065.0369/P369-A	3229
24998 7	7590 07/03/2006		EXAMINER	
DICKSTEIN SHAPIRO MORIN & OSHINSKY LLP 2101 L Street, NW Washington, DC 20037			UMEZ ERONINI, LYNETTE T	
			ART UNIT	PAPER NUMBER
			1765	
•			DATE MAILED: 07/03/2000	5

Please find below and/or attached an Office communication concerning this application or proceeding.

		LA C. A. No.				
		Application No.	Applicant(s)			
Office Action Summary		10/006,704	TRAPP, SHANE J.			
		Examiner	Art Unit			
		Lynette T. Umez-Eronini	1765			
Period fo	 The MAILING DATE of this communication apport Reply 	pears on the cover sheet with t	the correspondence address			
WHIC - Exte after - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REPL CHEVER IS LONGER, FROM THE MAILING D Insions of time may be available under the provisions of 37 CFR 1.1 SIX (6) MONTHS from the mailing date of this communication. O period for reply is specified above, the maximum statutory period are to reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailined patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 136(a). In no event, however, may a reply will apply and will expire SIX (6) MONTHS e, cause the application to become ABANE	TION. be timely filed from the mailing date of this communication. DONED (35 U.S.C. § 133).			
Status						
1)⊠	Responsive to communication(s) filed on 13 J	<u>une 2006</u> .				
2a) <u></u>	This action is FINAL . 2b)⊠ This	nis action is non-final.				
3)[Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
	closed in accordance with the practice under E	Ex parte Quayle, 1935 C.D. 1	1, 453 O.G. 213.			
Disposit	ion of Claims					
4)⊠	Claim(s) 26 and 77-82 is/are pending in the ap	oplication.				
	4a) Of the above claim(s) is/are withdrawn from consideration.					
5)	Claim(s) is/are allowed.					
6)⊠	Claim(s) 26 and 77-82 is/are rejected.					
7)	Claim(s) is/are objected to.					
8)□	Claim(s) are subject to restriction and/o	or election requirement.				
Applicati	ion Papers					
9)[The specification is objected to by the Examine	er.				
·	The drawing(s) filed on 10 December 2001 is/a		piected to by the Examiner.			
,	Applicant may not request that any objection to the	•	· ·			
	Replacement drawing sheet(s) including the correct					
11)	The oath or declaration is objected to by the Ex	xaminer. Note the attached Of	ffice Action or form PTO-152.			
Priority ι	under 35 U.S.C. § 119					
	Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority document	ts have been received.				
	2. Certified copies of the priority document	·	· · · · · · · · · · · · · · · · · · ·			
	3. Copies of the certified copies of the prio application from the International Bureau		elved in this National Stage			
* 5	See the attached detailed Office action for a list		aived			
		or the defined copies not rec	eiveu.			
Attachmen	t(s)					
	e of References Cited (PTO-892)	4) Interview Sumr				
3) 🔯 Inforr	e of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) r No(s)/Mail Date <u>2/16/2006</u> .		ail Date nal Patent Application (PTO-152)			

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DETAILED ACTION

REQUEST FOR CONTINUED EXAMINATION

1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114 because the formerly applied reference failed to teach a plasma etching composition comprising: at least two fluorocarbons are selected from the group consisting of fluorohydrocarbons, chlorofluorocarbons, and chlorofluorohydrocarbons. Applicant's submission filed on 6/13/2006 has been entered.

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was

not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

4. Claims 26, 77, 78, 81, and 82 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yang et al. (US 5,976,222).

Yang discloses, " . . . a fluorochemical containing exhaust gas from a semiconductor fabrication facility conducting an etch or clean process step is provided in stream **12** comprising a diluent gas, such as nitrogen, and fluorochemicals comprising potentially NF₃, SF₆, CF₄, CHF₃, CH₃F, C₂F₆, C₂HF₅, C₃F₈, C₄F₈, HF, F₂ and mixtures of these gases. Additional components in this mixture include; CO, CO₂, H₂O, O₂, CH₄, SiF₄, SiH₄, COF₂, N₂O, NH₃, O₃, Ar, Br₂, BrCl, CCl₄, Cl₂, H₂, HBr, HCl, He and SiCl₄ (column 7, lines 12). The aforementioned reads on,

A plasma etching composition.

Yet, Yang fails to disclose respectively in claims 26, 77, and 81-82, an example of Applicants' specific combination of two fluorocarbons and ammonia, wherein at least two fluorocarbons are selected from the group consisting of fluorohydrocarbons, chlorofluorocarbon, and chlorofluorohydrocarbons; at least one fluorocarbon, ammonia and oxygen; and at least one of oxygen and nitrogen, in addition to the rest of the limitations of claims 26 and 78.

However, it would have been obvious to one having ordinary skill in the art at the time the invention was made to select any combination of etchant gases as taught in the Yang reference, including Applicants' claimed etchants that would effectively

accomplish the disclosed composition since Applicants have not shown evidence of unexpected results.

Furthermore, since a gas is matter that occupies space and has random motion and since Yang discloses a mixture of etchant gases, then it would have been obvious that Yang's combination of fluorochemical gases and additional gases such as NH₃ and O₂ would result to form a reactive mixture, **as recited in claims 26, 77 and 78**.

5. Claims 79 and 80 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yang (US '222) as applied to claim 78 above, and further in view of Smith (US 6,277,733 B1).

While Yang fails to disclose wherein at least one of said at least two fluorocarbons is CH_2F_2 , in claim 79 and wherein said at least two fluorocarbons are CF_4 , CHF_3 , and CH_2F_2 , in claim 80.

Smith discloses a wafer is subjected to a plasma containing other fluorocarbons, such as C₂F₆, CHF₃, CH₂F₂ (column 4, lines 34-37).

Hence, it would have been obvious to one having ordinary skill in the art at the time the invention was made to modify Yang by selecting any combination of fluorocarbon etchants in the Smith reference for the purpose of removing hydrocarbon residue left on metal structure (column 4, lines 41-43).

Response to Arguments

6. Applicant's arguments with respect to claims 26-29, 31, and 71 have been considered but are most in view of the new ground(s) of rejection because the formerly applied reference fail to teach: A plasma etching composition --comprising--:

. . . --wherein said at least two fluorocarbons are selected from the group consisting of fluorohydrocarbons, chlorofluorocarbons, and chlorofluorohydrocarbons--, as recited in claim 26;

at least one fluorocarbon, oxygen, and ammonia, wherein said at least one fluorocarbon, said --oxygen--, and said ammonia form a reactive mixture, as recited in (Currently Amended) Claim 77; and

the limitations of (New) Claims 78-82.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Lynette T. Umez-Eronini whose telephone number is 571-272-1470. The examiner is normally unavailable on the First Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571-272-1465. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only.

For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

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June 24, 2006

NADINE NONTON
SUPERVISORY PATENT EXAMINER
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